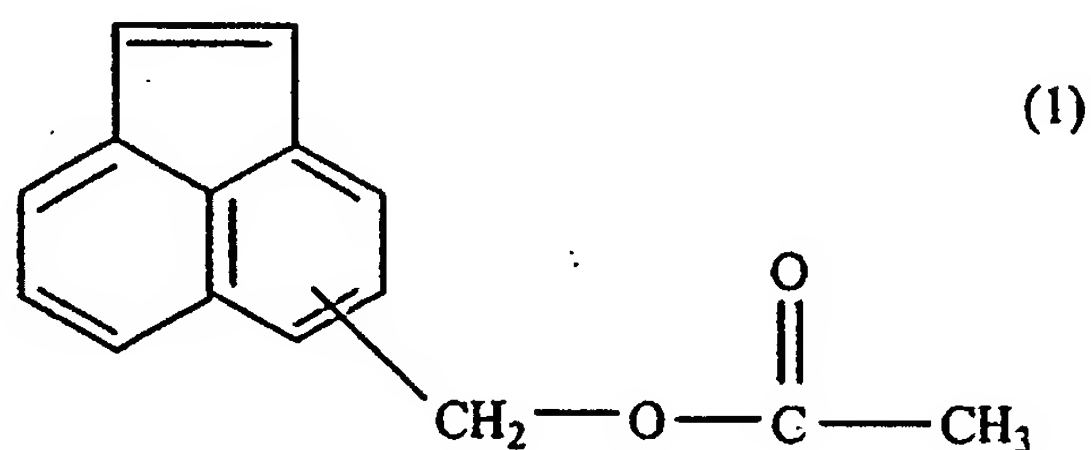


**Amendments to the Claims:**

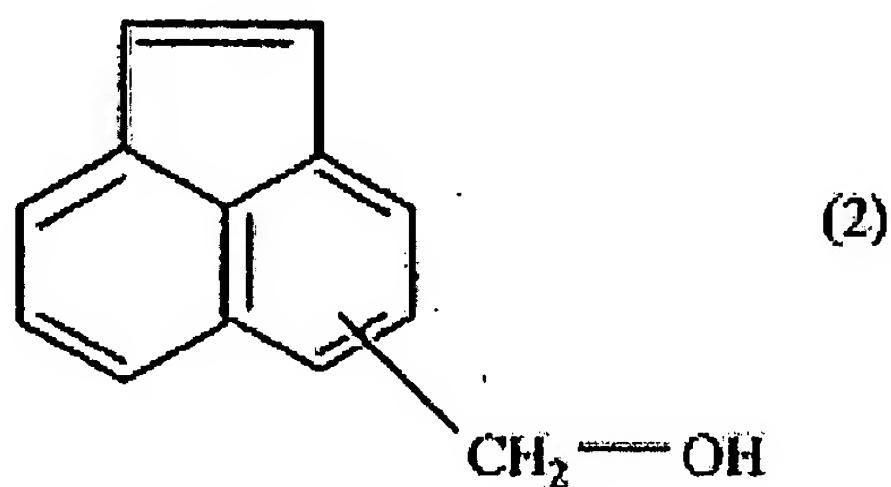
This listing of claims will replace all prior versions and listings of claims in the application.

**Listing of Claims:**

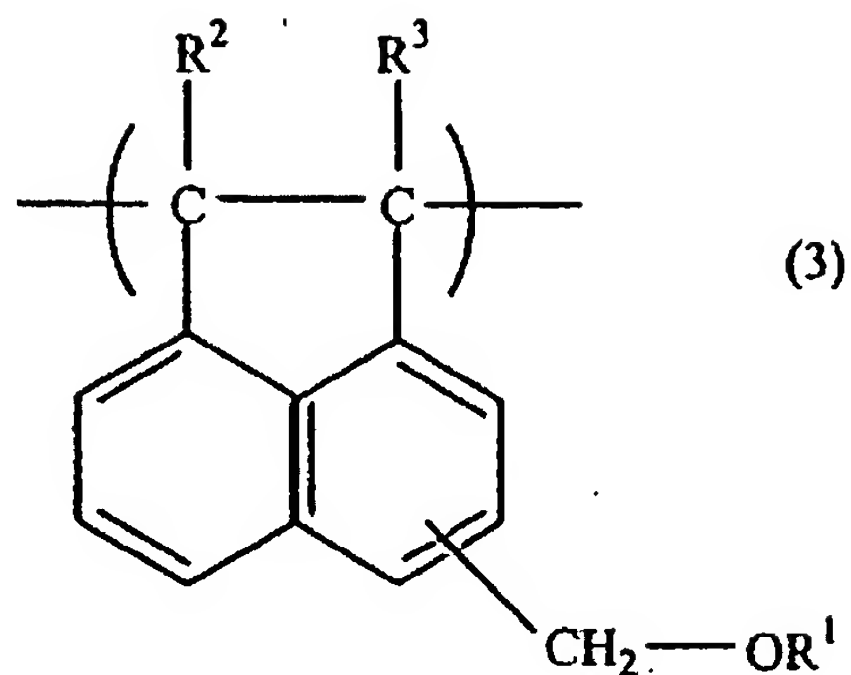
1. (Previously presented) Acetoxymethylenaphthylene of the following formula (1)



2. (Previously presented) Hydroxymethylenaphthylene of the following formula (2)



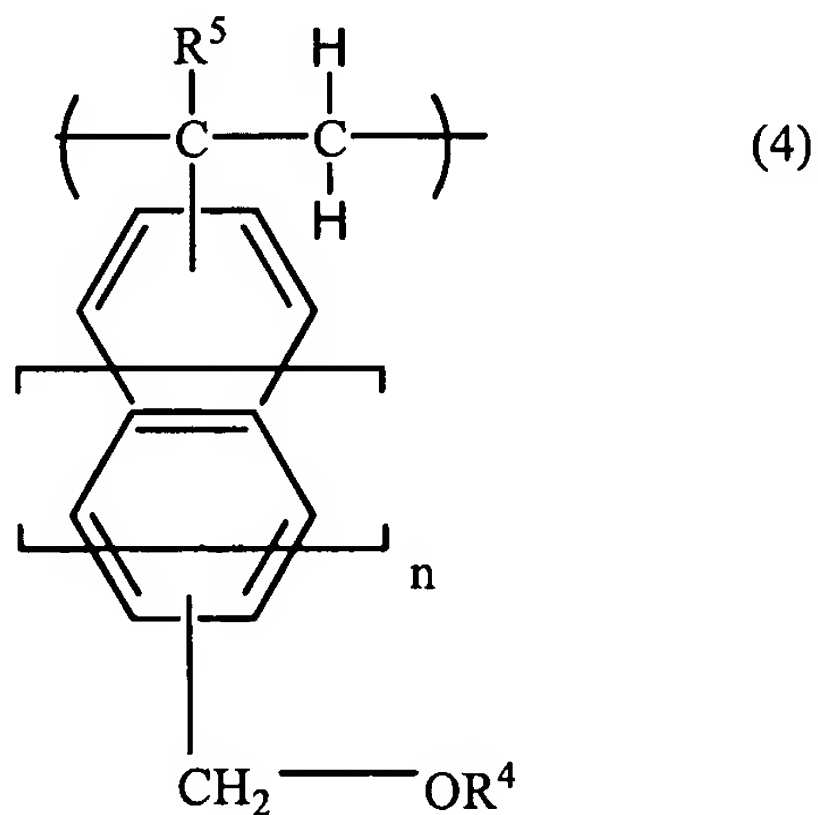
3. (Original) A polymer containing a structural unit of the following formula (3),



wherein R<sup>1</sup> is a hydrogen atom and R<sup>2</sup> and R<sup>3</sup> individually represent a monovalent atom or a monovalent organic group, the polymer having a polystyrene-reduced weight average molecular weight determined by gel permeation chromatography (GPC) in the range of 500 to 10,000.

4. (Original) An antireflection film-forming composition comprising the polymer of Claim 3 and a solvent.

5. (Currently Amended) An antireflection film-forming composition comprising, a polymer having a structural unit of the following formula (4)

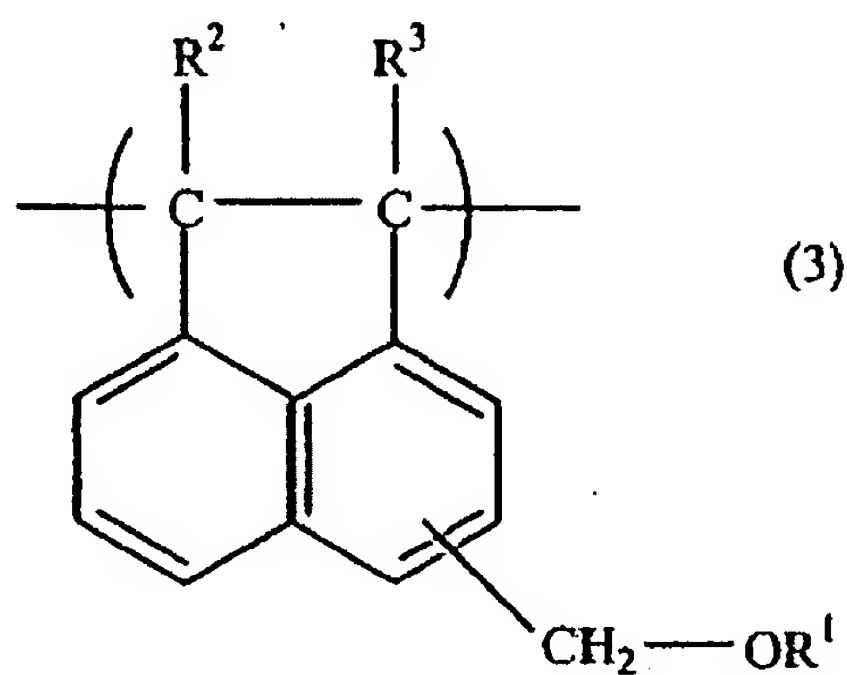


wherein  $R^4$  is a monovalent organic group selected from the group consisting of a phenyl group, an alkyl group, an alkenyl group, an acyl group, and a group in which one or more hydrogen atoms of a phenyl group, an alkyl group, an alkenyl group, or an acyl group are replaced by one or more of the same or different substituents selected from the group consisting of a halogen atom, a hydroxyl group, a mercapto group, a nitro group and a sulfonic acid group,  $R^5$  is a monovalent atom or a monovalent organic group, and  $n$  is [[0 or]] 1, and

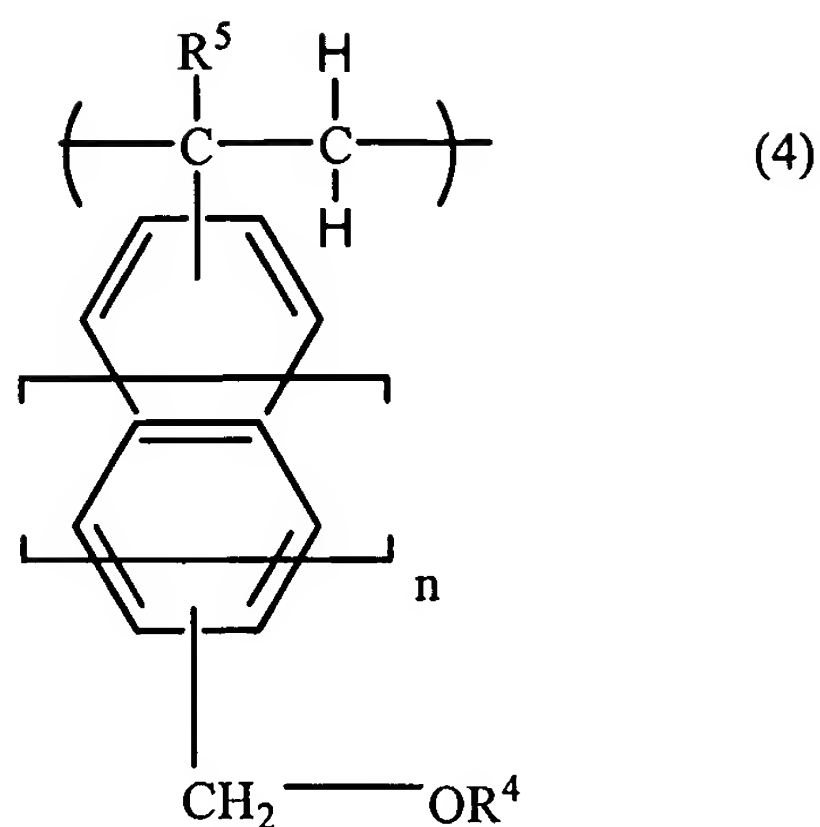
a solvent.

6. (Previously Presented) An antireflection film-forming composition comprising,

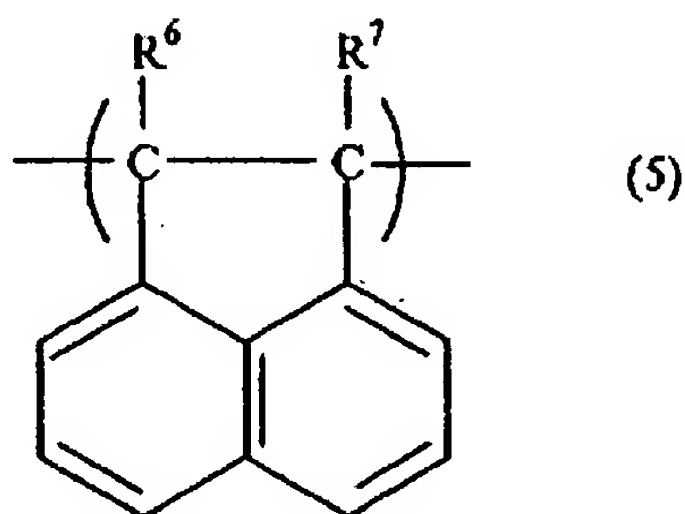
at least one polymer selected from the group consisting of: a polymer having a structural unit of the following formula (3)



wherein  $R^1$  is a hydrogen atom and  $R^2$  and  $R^3$  individually represent a monovalent atom or a monovalent organic group and a structural unit of the following formula (4)



wherein R<sup>4</sup> is a hydrogen atom or a monovalent organic group, R<sup>5</sup> is a monovalent atom or a monovalent organic group, and n is 0 or 1; a polymer having a structural unit of the formula (3) and a structural unit of the following formula (5)



wherein R<sup>6</sup> and R<sup>7</sup> individually represent a monovalent atom or a monovalent organic group; and a polymer having a structural unit of the formula (4) and a structural unit of the formula (5); and

a solvent.

7. (Original) The antireflection film-forming composition according to Claim 4, further comprising an acid generator.

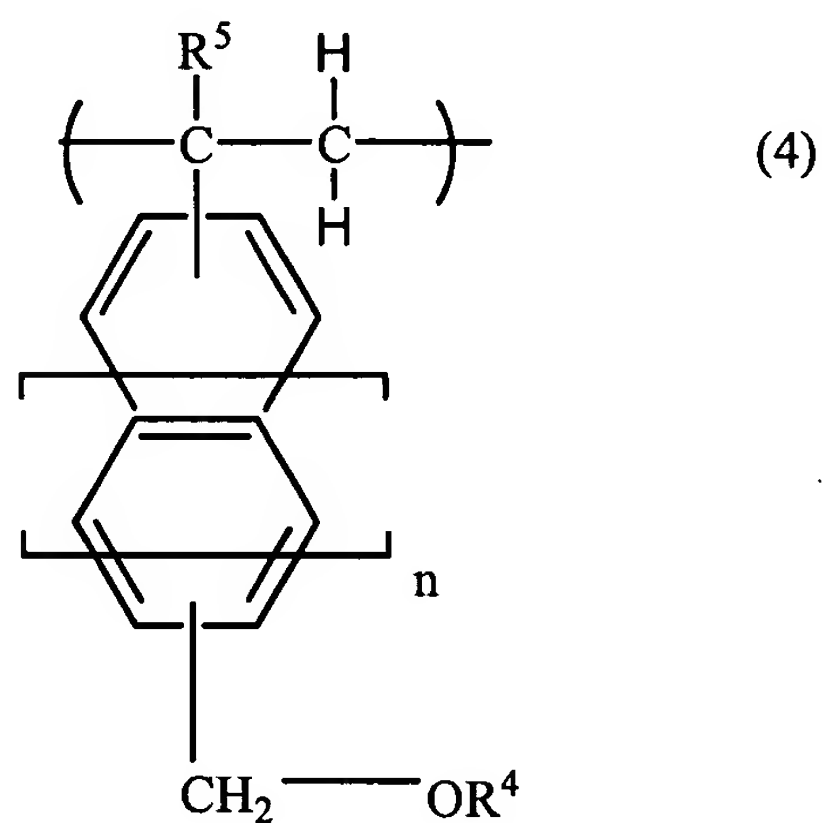
8. (Original) The antireflection film-forming composition according to Claim 5, further comprising an acid generator.

9. (Original) The antireflection film-forming composition according to Claim 6, further comprising an acid generator.

10. (Canceled).

11. (Previously presented) An antireflection film-forming composition comprising:

a polymer having a structural unit of the following formula (4);

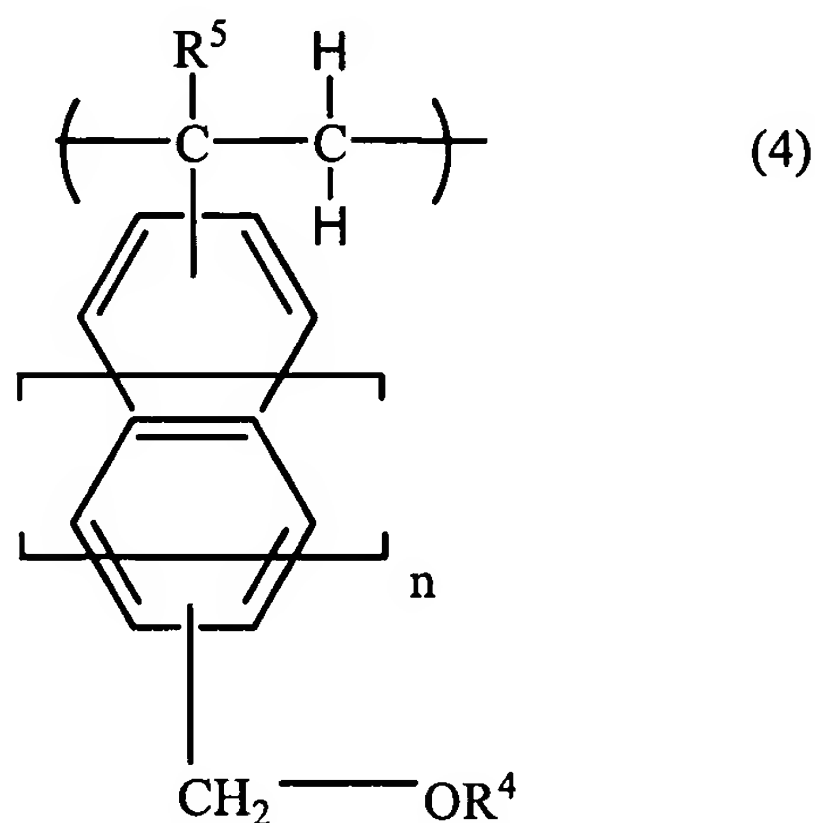


wherein  $\text{R}^4$  is a hydrogen atom or a monovalent organic group and  $\text{R}^5$  is a monovalent atom or a monovalent organic group; and

a solvent.

12. (Previously presented) The antireflection film-forming composition according to Claim 11, further comprising an acid generator.

13. (New) An antireflection film-forming composition comprising,  
a polymer having a structural unit of the following formula (4)



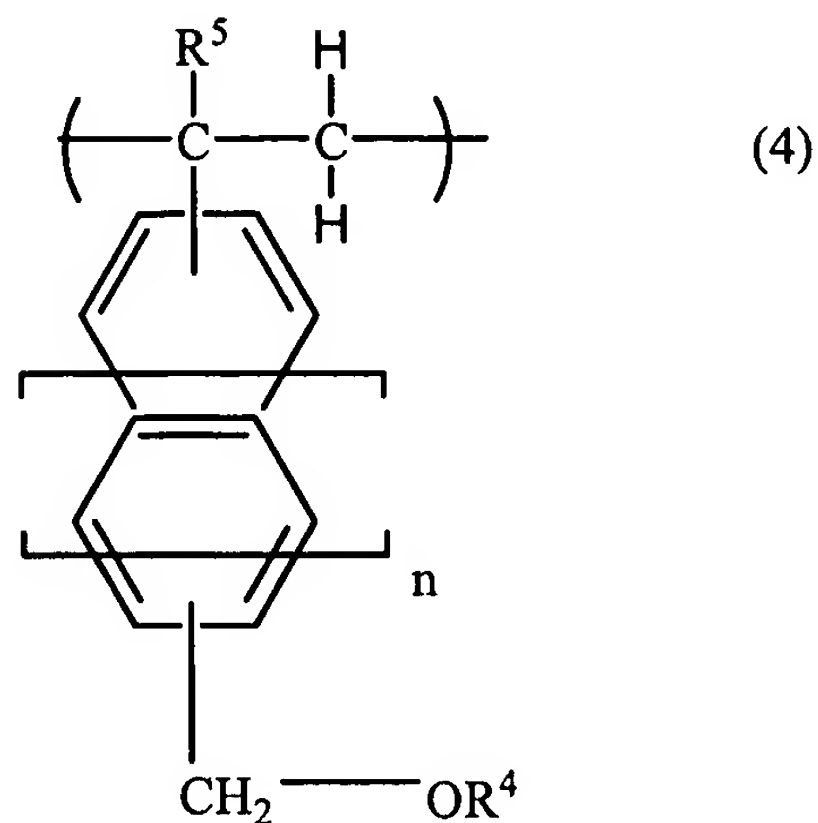
wherein R<sup>4</sup> is a monovalent organic group selected from the group consisting of a phenyl group, an alkenyl group, an acyl group, and a group in which one or more hydrogen atoms of a phenyl group, an alkyl group, an alkenyl group, or an acyl group are replaced by one or more of the same or different substituents selected from the group consisting of a halogen atom, a hydroxyl group, a mercapto group, a nitro group and a sulfonic acid group, R<sup>5</sup> is a monovalent organic group, and n is 0 or 1, and

a solvent.

14. (New) The antireflection film-forming composition according to Claim 13, further comprising an acid generator.

15. (New) An antireflection film-forming composition comprising,

a polymer having a structural unit of the following formula (4)



wherein  $\text{R}^4$  is a monovalent organic group selected from the group consisting of an alkenyl group and a group in which one or more hydrogen atoms of a phenyl group, an alkyl group, an alkenyl group, or an acyl group are replaced by one or more of the same or different substituents selected from the group consisting of a halogen atom, a hydroxyl group, a mercapto group, a nitro group and a sulfonic acid group,  $\text{R}^5$  is a monovalent atom or a monovalent organic group, and  $n$  is 0 or 1, and

a solvent.

16. (New) The antireflection film-forming composition according to Claim 15, further comprising an acid generator.